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**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q76671

Shih-Fan WANG, et al.

Appln. No.: 10/624,487

Group Art Unit: 1752

Confirmation No.: 7818

Examiner: John S. Y. Chu

Filed: July 23, 2003

For: POSITIVE PHOTOSENSITIVE COMPOSITION AND METHOD OF PATTERN  
FORMATION USING THE SAME

**RESPONSE UNDER 37 C.F.R. § 1.111**

**MAIL STOP AMENDMENT**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

This Response is to the Office Action mailed July 7, 2004.

Claims 1-11, 13-28, and 30-33 are rejected under 35 U.S.C. 102(e) as allegedly being anticipated by TOMIKAWA et al. '764. Claims 1-33 are rejected under 35 U.S.C. 103 as allegedly being unpatentable over TOMIKAWA et al. Applicants respectfully traverse the rejections for the reasons discussed below.

The present application features, as claim 1 recites, a positive photosensitive composition comprising a poly(imide-benzoxazole) precursor prepared by the reaction of a trimellitic anhydride halide monomer with a bis(o-diaminophenol) monomer, a photosensitizer, and a solvent. The characteristic poly(imide-benzoxazole) includes at least a repeating unit as: